

Notice of References Cited	Application/Control No. 10/543,141		Applicant(s)/Patent Under Reexamination AIZAWA ET AL.	
	Examiner MARIANNE L. PADGETT		Art Unit 1792	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,272,015 A	12-1993	Hamdi et al.	428/472
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	DE 198 15 019 A1	10-1999	Germany	Naumann et al.	C23C 8/24
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	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Kim et al., Derwent abstract ACC-No.2001-548299 of Korean publication KR 200102 8157, published 4/6/2001, titled "method for preparing aluminum nitride by using plasma and device thereof", classification C01F 7/66
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.